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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: KOSHELEV et al.

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of

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Examiner: NOT ASSIGNED

Group Art Unit:

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
<i>W</i>	AR	4,494,043	01/1985	Stallings et al.			
<i>W</i>	BR	4,644,576	02/1987	Kuyel			
<i>W</i>	CR	6,414,438	07/2002	Borisov et al.			
	DR						
	ER						
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	GR						
	HR						
	IR						
	JR						
	KR						
	LR						
	MR						
	NR						

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name		Abstract		Readily Available	
							Enclosed	No	Enclose	No
	OR	0 480 617 A2	10/1991	Europe	Jewell et al.					
	PR									
	QR									
	RR									
	SR									
	TR									
	UR									

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

<i>W</i>	VR	Patent Abstracts of Japan, Publication No. 62176038, August 1, 1987.				
<i>W</i>	WR	Bergmann, K., et al., "Highly Repetitive, Extreme-Ultraviolet Radiation Source Based on a Gas-Discharge Plasma," <i>Applied Optics</i> , Vol. 38, No. 25, September 1, 1999, pp. 5413-17.				
<i>W</i>	XR	Va'vra, J., et al., "Soft X-Ray Production in Spark Discharges in Hydrogen, Nitrogen, Air, Argon and Xenon Gases," <i>Nuclear Instruments & Methods in Physics Research, Section A</i> , Vol. 418, No. 2-3, December 1998, pp. 405-419.				
<i>W</i>	YR	Melnichuk et al., "Plasma Focus Light Source with Improved Pulse Power System," Pub. No: US 2003/0006383 A1, published January 9, 2003				

Examiner

ZIA R. HASHMI

Date Considered:

3/1/04

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.